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# Loss analysis in nitride deep ultraviolet planar cavity

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<sup>b</sup> Université Côte d'Azur, CNRS, CRHEA, 06560 Valbonne, France **Abstract.** A deep ultraviolet (DUV) nitride planar micro cavity with a double-side  $\text{HfO}_2/\text{SiO}_2$  DBR structure was fabricated. An AlGaIn-based quantum dots (QDs) epilayer was used as the active layer. The epilayers were grown by molecular beam epitaxy (MBE) on sapphire substrate with a thin GaN buffer. Cavity modes at 305, 314, 323 and 335 nm were observed by photoluminescence. Optical losses of the order of  $10^3 \text{ cm}^{-1}$  were deduced from the Q value of the cavity modes. An analysis of the surface scattering losses and absorption of the epilayer was performed. The result suggests that surface scattering from the surface roughness appearing after LLO is the main cause for optical loss,. A method is proposed to reduce the impact of scattering loss by placing the roughness layer at the node of the optical field.

**Key words:** UV cavity, optical loss, AlGaIn-based QDs

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## 1 Introduction

III-nitrides based on  $\text{Al}_x\text{Ga}_{1-x}\text{N}$  have attracted a lot of attention for promising applications in optoelectronic devices such as ultraviolet laser-diodes (UV-LDs), that have many applications such as high density optical storage, sterilization of water, biological detection and photolithography.  $\text{Al}_x\text{Ga}_{1-x}\text{N}$  can be used in the ultraviolet regime, with its direct bandgap ranging from 3.4 to 6.0 eV at room temperature by adjusting the Al component<sup>[1]</sup>. In the last few years, AlGaIn-based deep ultraviolet (DUV) edge-emitting lasers have been demonstrated <sup>[2-14]</sup>, with wavelengths ranging from 214 nm<sup>[4]</sup> to 368.4 nm<sup>[5]</sup>. The shortest lasing wavelength of electrically injected AlGaIn-based laser, at present, is 336 nm<sup>[6]</sup>.

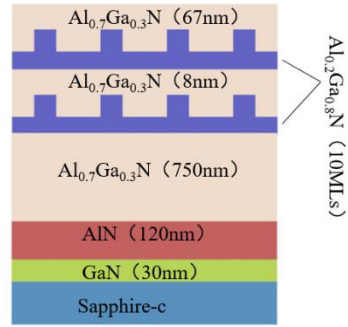
Comparing with edge-emitting lasers, vertical-cavity surface-emitting lasers

(VCSELs) have many advantages such as 1) low power consumption, 2) large scale 2D array, 3) single longitudinal mode operation, 4) circular beam for direct fiber coupling,.....<sup>[15]</sup>. Therefore, the development of UV VCSELs is also very important. VCSELs were firstly proposed by Professor Emeritus Kenichi Iga in 1977<sup>[16-18]</sup>. The VCSEL lasing action was firstly obtained near 1.2  $\mu\text{m}$  at 77 K in 1979<sup>[19]</sup>. In recent years, VCSELs have been put to the blue and green range<sup>[20-26]</sup> using III-nitride semiconductors. However, there were rare reports about VCSELs operating in the UV regime<sup>[27-30]</sup>, and none in the DUV range. And the shortest wavelength optically pumped GaN-based VCSEL reported was operated at 363 nm at 300 K with a threshold of 2 MW/cm<sup>2</sup><sup>[29]</sup>. All of these epilayers were grown directly on nitride DBRs, and then covered by a dielectric DBR<sup>[28, 30]</sup> or a nitride DBR<sup>[29]</sup>. Nitride DBRs are generally characterized by a small refractive index contrast and narrow stop-band width. This will also decrease the confinement factor, due to the large penetration depth of light in nitride DBRs. To get high reflectivity, the period number of DBRs needs to be quite high. It increases the difficulty in material growth. Double-side dielectric DBR structures, by contrast, are preferable. DUV VCSEL operation is also limited by the sub-bandgap absorption in the cavity.

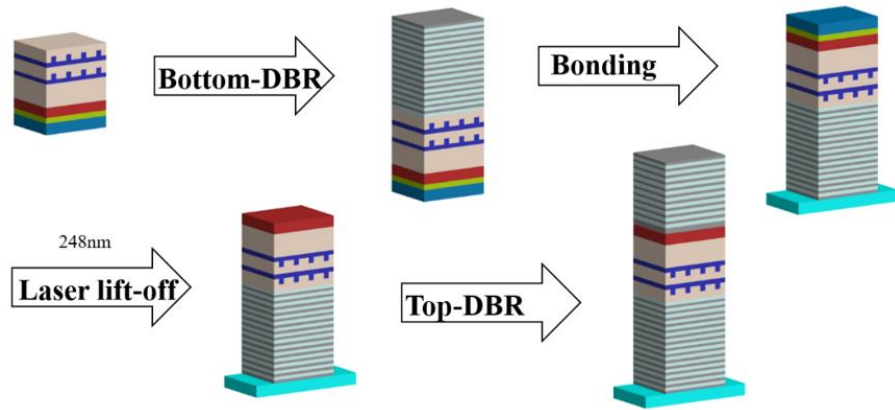
In this work, a DUV double-side dielectric DBR structure planar cavity is reported. Optical losses of the DUV cavity modes were analyzed to be in the  $10^3 \text{ cm}^{-1}$  range. Theoretical calculations suggest that the scattering loss from the surface, i.e. a roughening of the layer caused by laser lift-off, is the main cause for cavity loss. Fabrication of low-loss DUV resonant cavity is finally discussed.

## 2 Experimental details

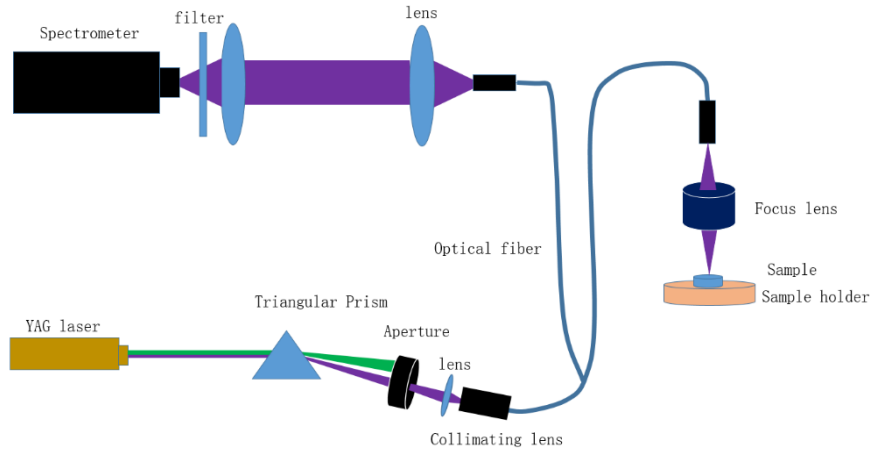
The AlGaIn quantum dots (QDs) epilayer was grown on c-plane sapphire by molecular beam epitaxy (MBE) in a RIBER 32 P reactor, following the growth conditions described in ref. [S. Matta, J. Brault, T. H. Ngo, B. Damilano, M. Korytov, P. Vennéguès, M. Nemoz, J. Massies, M. Leroux, and B. Gil, “Influence of the heterostructure design on the optical properties of GaN and Al<sub>0.1</sub>Ga<sub>0.9</sub>N quantum dots for ultraviolet emission” J. Appl. Phys. 122, 085706 (2017)]. As shown in Fig. 1, the 30 nm GaN layer was used as a buffer layer and sacrificial layer in the laser lift-off process. Fabrication of the microcavity was then carried out with first coating with a 15 pairs of HfO<sub>2</sub>/SiO<sub>2</sub> bottom-DBR, with a peak reflectivity of 98.01% and a bandwidth of ~70 nm, on the top of the sample. It is wider than that of nitride DBR with a peak reflectivity of 98.01% and a bandwidth of 11 nm<sup>[30]</sup>. After that, the sample was bonded to a quartz glass, faced to bottom-DBR, by wax. And the most important processing technique—laser lift-off (LLO)- was performed with a 248 nm KrF excimer laser to remove the sapphire substrate. Molten Ga was then removed by diluted hydrochloric acid. After that, a 10.5 pairs of HfO<sub>2</sub>/SiO<sub>2</sub> top-DBR, with a peak reflectivity of 96.81% and a bandwidth of 69 nm, was deposited on AlN, assuming the whole GaN layer decomposed during LLO. The whole process is schematized in Fig. 2. PL measurements were performed by using the 4th harmonic of a Q-switched Nd: YAG laser with the wavelength of 266 nm as the pumping source. The signal was collected and analyzed by using a spectrometer. The schematic diagram of the PL set-up is depicted in Fig. 3.



**Fig. 1** Schematic diagram of the epilayer



**Fig. 2** Diagram of the whole process of fabricating the micro cavity



**Fig. 3** Schematic diagram of the PL set-up used in this study, a 266 nm wavelength was used as

pumping source.

## Results and discussion

The PL results are depicted in Fig. 4. One can see that 4 cavity modes are clearly

observed at 305, 314, 323 and 335 nm. Interval among these modes is around 10 nm.

The Q value of every mode could be calculated according to equation (1),

$$Q = \lambda_0 / \Delta\lambda, \quad (1)$$

where  $\lambda_0$  is the peak wavelength of the emission mode, and  $\Delta\lambda$  its full width of half maximum. The results are listed in Table 1.

**Table 1** Q values and internal cavity losses of every cavity mode

Mode (nm)	305	314	323	335
Q value	166.58	127.32	194.79	160.78
$\alpha$ (cm <sup>-1</sup> )	2671.8	3421.9	2102.5	2363.5

Obviously, the Q values are were low, indicating strong optical losses in the cavity.

These optical losses can be deduced from Q according to equation (2),

$$Q = 2\pi \frac{nL_{eff}}{\lambda} \left( \frac{1}{\ln(R_{b\_DBR}R_{t\_DBR})^{-1/2} + L_{eff}\alpha} \right), \quad (2)$$

where  $n$  is the cavity refractive index,  $L_{eff}$  is the effective cavity length,  $\lambda$  is the wavelength,  $\alpha$  is the internal cavity loss,  $R_{t\_DBR}$  and  $R_{b\_DBR}$  are the top and bottom DBR reflectivities, respectively. The effective cavity length  $L_{eff}$  is longer than the nominal thickness of the epilayer, due to the limited controllability, and could be obtained from equation (3),

$$\nu_{q+1} - \nu_q = \frac{c}{2nL_{eff}}, \quad (3)$$

where  $q$  is the longitudinal mode order,  $\nu$  is the longitudinal mode frequency,  $c$  is the vacuum light velocity.  $L_{eff}$  was then evaluated to be 2288 nm. And cavity losses of every mode were 2671.8, 3421.9, 2102.5, and 2363.5 cm<sup>-1</sup> for the 305, 314, 323, and 335 nm modes, respectively (Table 1). If the cavity loss reduces to 195 cm<sup>-1</sup>, the Q

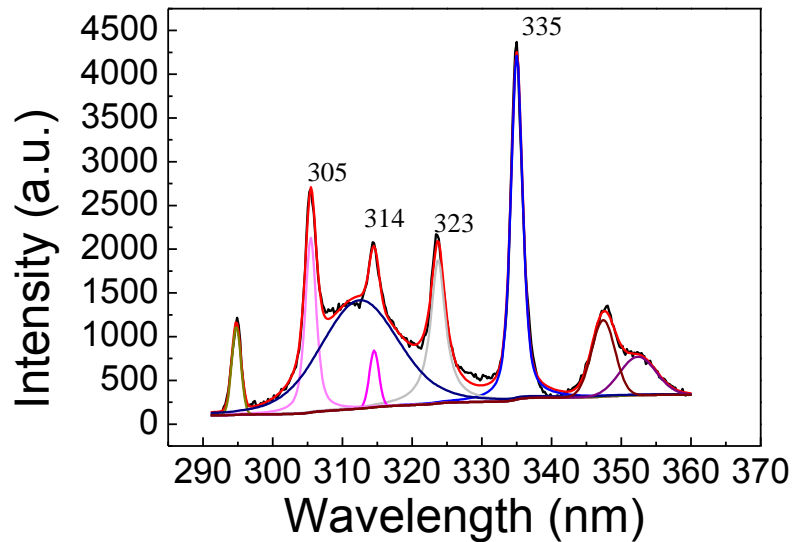
value will reach 1500.

Fig. 5 depicts the simulated cavity modes distributions and the refractive index profile. Simulated effective cavity lengths ( $L_{eff}$ ), corresponding to every mode, can also be obtained from these curves between the two positions where the optical intensity decreases to  $1/e$ , and the confinement factors ( $\Gamma_r$ ) are then also obtained. The definition of the confinement factor is :

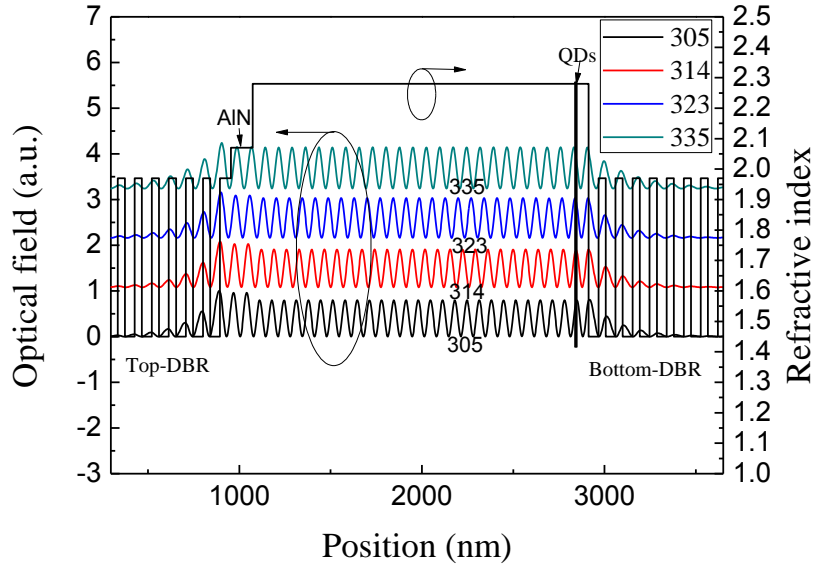
$$\Gamma_r = \frac{L_{eff}}{d_a} \frac{\int_{d_a} |E(z)|^2 dz}{\int_{L_{eff}} |E(z)|^2 dz}, \quad (4)$$

where  $d_a$  is active region thickness,  $E(z)$  is the electric field intensity along the z axis.

The results are listed in Table 2. A  $\Gamma_r$  value close to 2 suggests that the active region is perfectly aligned to the antinode of the cavity mode.



**Fig. 4** Emission spectra of the micro cavity at which temperature ?



**Fig. 5** Simulated cavity modes distributions and refractive index profiles

**Table 2** Confinement factor, reflectance of bottom and top DBR and overlap area of the sample

Mode (nm)	305	314	323	335
$\Gamma_r$	1.71	1.89	1.88	1.62
$R_{b\_DBR}(\%)$	98.01	97.97	97.66	96.74
$R_{t\_DBR}(\%)$	96.81	96.64	95.70	91.56
OA	17.13	14.97	11.44	7.14

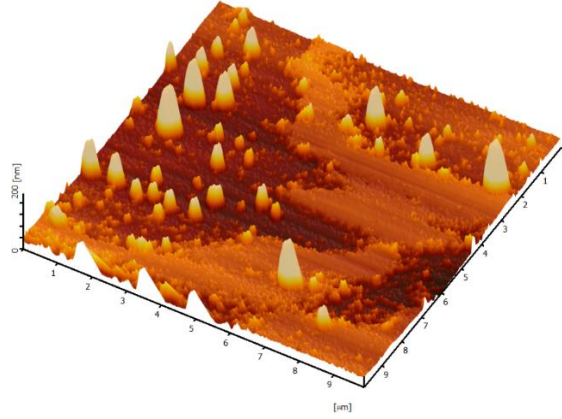
The surface morphology of the epilayer after LLO had been characterized by atomic force microscopy (AFM), as shown in Fig. 6. Over a  $10 \mu\text{m} \times 10 \mu\text{m}$  area, the root mean square (RMS) of the surface roughness was about 20.36 nm. When the surface roughness is far below the incident wavelength, scattering losses can be defined as the total integrated scattering (TIS)<sup>[31]</sup>, i.e. the ratio between scattering by surface and total reflection by surface, as in equation (5),

$$TIS = C \left\{ 1 - \exp \left[ - \left( \frac{4\pi\delta \cos \theta}{\lambda_0} \right)^2 \right] \right\}, \quad (5)$$

where  $\delta$  is the RMS of the surface roughness,  $\theta$  is the incident angle,  $\lambda_0$  is the wavelength, and C is a correction factor, which is equal to 0.96. If light travels from



the opposite direction,  $C$  will be  $1/0.96=1.04$ . For normal incidence ( $\theta=0$ ), the  $TIS$  for the 305, 314, 323 and 335 nm modes are 49%, 47%, 45% and 42%, respectively. It suggests that these roughness scattering losses dominate in the cavity losses.



**Fig. 6** Surface morphology of the epilayer after LLO characterized by AFM

The absorption of the epilayer, which was mainly composed of  $\text{Al}_{0.7}\text{Ga}_{0.3}\text{N}$  with an absorption coefficient about  $0.45 \times 10^3 \text{ cm}^{-1}$  near 320 nm<sup>[32]</sup>, was also calculated. The absorbance of the epilayer ( $A_{epi}$ ) could be evaluated according to equation (6),

$$A_{epi} = 1 - e^{-\alpha_{epi}d}, \quad (6)$$

where  $\alpha_{epi}$  is the absorption coefficient, and  $d$  is the layer thickness. The absorbance of the epilayer ( $A_{epi}$ ) through the thickness of the epilayer was 8.4%. The average percentage of optical losses ( $A_{ave}$ ) in a single round trip can be deduced from Fig. 7.

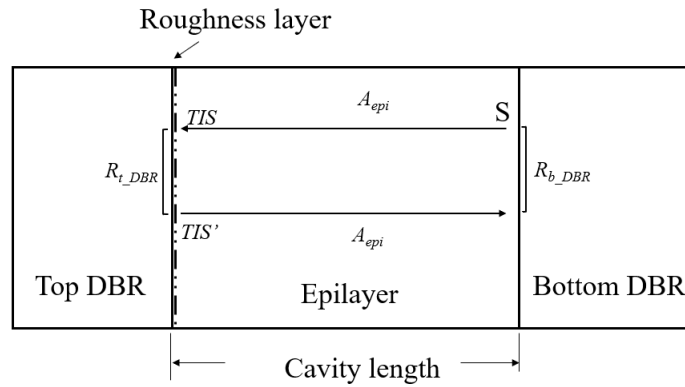
When light travels from the assumptive starting point,  $S$ ,  $A_{ave}$  is given as :

$$\begin{aligned} A_{ave} &= 1 - (1 - A_{epi})(1 - TIS)R_{t\_DBR}(1 - TIS')(1 - A_{epi})R_{b\_DBR} \\ &= 1 - (1 - A_{epi})^2(1 - TIS)(1 - TIS')R_{b\_DBR}R_{t\_DBR}, \end{aligned} \quad (7)$$

where  $R_{b\_DBR}$  and  $R_{t\_DBR}$  are the bottom and top DBR reflectivities, respectively, listed in Table 2.  $TIS'$  is when light travels in the opposite direction compared with  $TIS$ . And  $TIS'$  for 305, 314, 323 and 335 nm modes are 53%, 51%, 49% and 46%,

respectively. The absorbance of the DBR was omitted, since the values of the bottom and top DBR were negligible, i.e. respectively far below 0.9% and 3.0%, and therefore complicated to observe. The result was

$$A_{ave}=1-(1-8.4\%)^2(1-45.75\%)(1-49.75\%)*97.6\%*95.18\%=78.75\% . \quad (8)$$

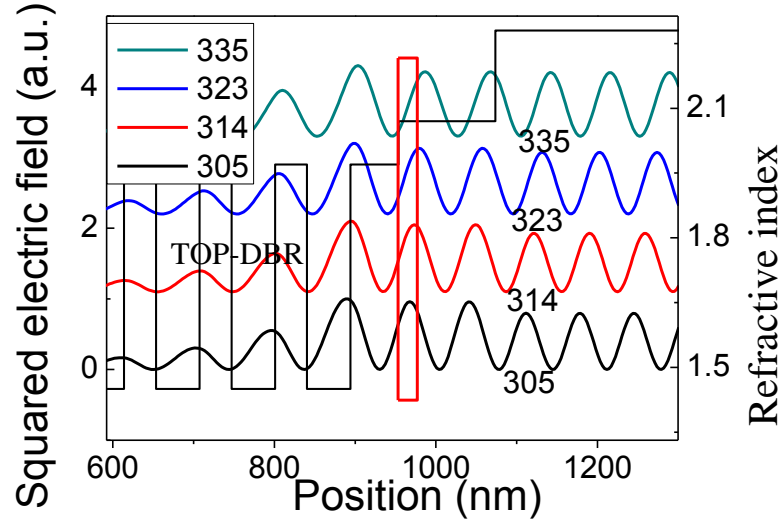


**Fig. 7** Schematic diagram of a single round trip of light traveling in the cavity

$A_{ave}$  has a huge value and will largely increase the threshold of lasing. Obviously, the  $TIS$  is the dominant factor in the optical losses of the cavity. If  $TIS$  and  $TIS'$  are omitted, the value of  $A_{ave}$  would decrease to 22.06%. If only  $TIS$  and  $TIS'$  were taken into account, the value would be equal to 72.74%. The next work should focus on reducing the  $TIS$ , i.e. on reducing the surface roughness.

To reduce the optical losses at the interface between the top-DBR and the epilayer, one method is proposed in the following. Fig. 8 represents a zoom of Fig. 5, i.e. the simulated cavity modes, with the red rectangle indicating the rough layer generated by LLO. It is shown that if this layer is properly placed at the node of the standing wave, the scattering losses will be minimized. Also, the LLO processing technique should be continuously improved to reduce the surface roughness: for instance, reducing its value to 1 nm should lead to a  $TIS$  of 0.0015 and the Q value will be increased to

around 700.



**Fig. 8 Investigation of the coupling of the** interfacial layer (see Fig. 7) between the top DBR and the epilayer (red rectangle) and the optical field in the laser cavity

At last, we focus on the observed peak intensity differences among these cavity modes. Fig. 4 shows that the optical intensity of the 335 nm mode is the strongest, followed by the 323 nm mode, the third is the 305 nm mode, and the 314 nm mode is the weakest. Calculations of overlap areas (OA) of the optical field of each cavity mode with the (rough) interfacial layer are performed, from Fig. 8 simulations. The results are listed in Table 2. These values can be used to evaluate the influence of the scattering losses on the cavity modes, i.e. the bigger the value is, the greater impact it has. Obviously, the OA of 314 nm, 323 nm and 335 nm modes are decreasing with the wavelength increase, which means that the impact of the scattering losses is larger for the 314 nm mode, in agreement with our results. However, the 305 nm mode presents an abnormal behaviour, since its intensity is higher than that of the 314 nm mode. At this stage, the origin of this characteristic is still unclear. Regarding the

335nm mode of smaller Q value than that of the 323 nm mode, it could be attributed to the lower reflectivities of the DBRs. In addition, according to equation (5), scattering losses also increase with decreasing wavelength and actually the 314 nm, 323 nm and 335 nm modes all followed this rule. In our study, except for the 305 nm mode, OA and scattering losses have been found to increase with decreasing wavelength.

## **Conclusions**

To sum up, an AlGaIn-based QDs microcavity with double-sided dielectric DBRs structure was fabricated and optical losses were analyzed. The optical loss was  $10^3 \text{ cm}^{-1}$  in magnitude and found to be mainly caused by surface roughness scattering after the LLO process. Improvements for reducing the surface scattering losses were proposed by properly placing the epilayer – top DBR interface at a node of the optical field.

## **Acknowledgements**

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